

MOSFET IV Characteristics

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Executive Summary: The analysis of the output vs input (transfer) relationships of the

MOSFET shows a nonproportional relationship between input voltage V_{gs} and output voltage

I_{ds} . When the former is increased, the latter increases exponentially, which confirms the

saturation mode equation $I_d = (K_n/2)(V_{gs}-V_{tn})^2$ from theory. The relationship between V_{ds}

and I_d is variable, MOSFET behavior changes depending on the mode. In cutoff, I_d and V_{ds} are

0 because V_{gs} has not overcome V_{tn} . In saturation, when V_{ds} increases are large, I_d increases

are small, assuming real conditions, and approaching none assuming ideal conditions. In linear,

as V_{ds} increases, I_{ds} has larger increases, and the two form a sloped line indicating a constant

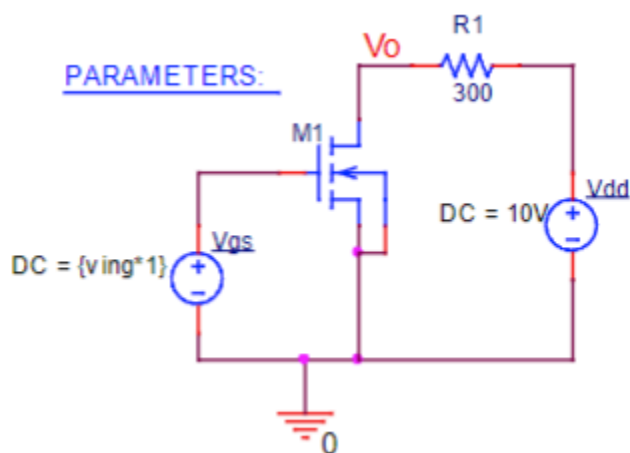
resistance.

Objective: To study the transfer characteristics of the Metal Oxide Semiconductor Field

Effect Transistor (MOSFET) through laboratory experiments and PSpice simulation.

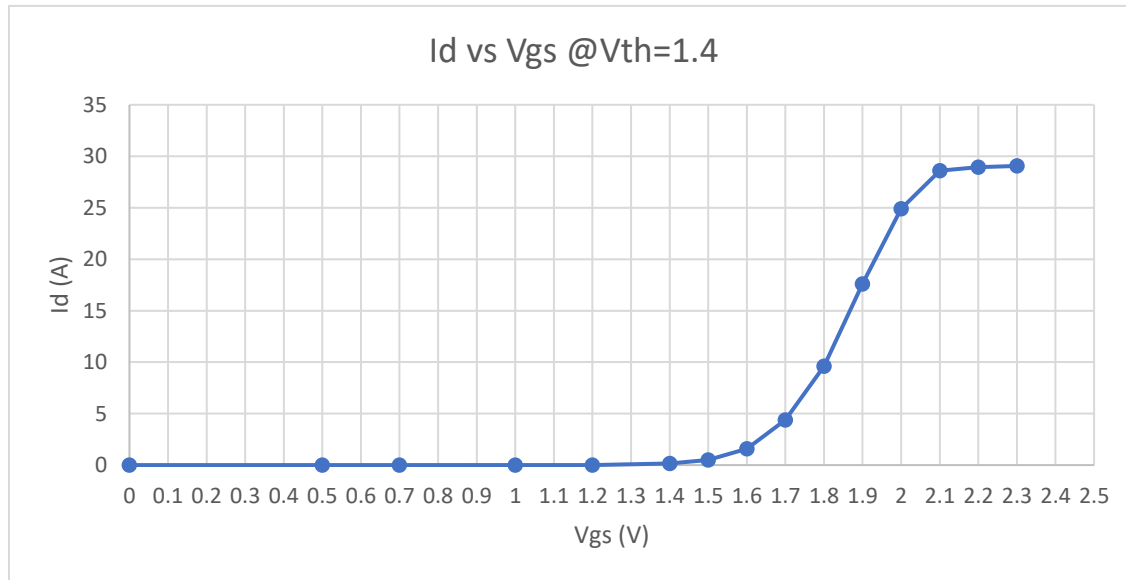
Figure 1 (LAB)

Schematic

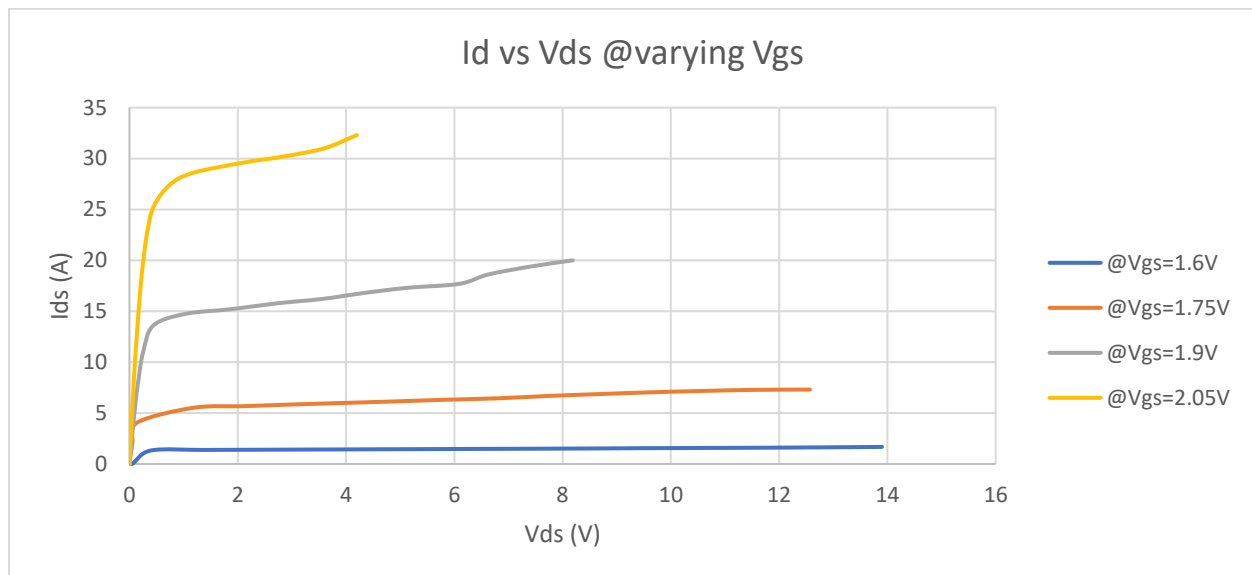


Excel Generated Plots

Plot I_d vs V_{gs} , identify V_{th} . Graphically, $V_{th}=1.4V$, the point that indicates that the MOSFET is entering saturation and I_d is beginning to increase exponentially.



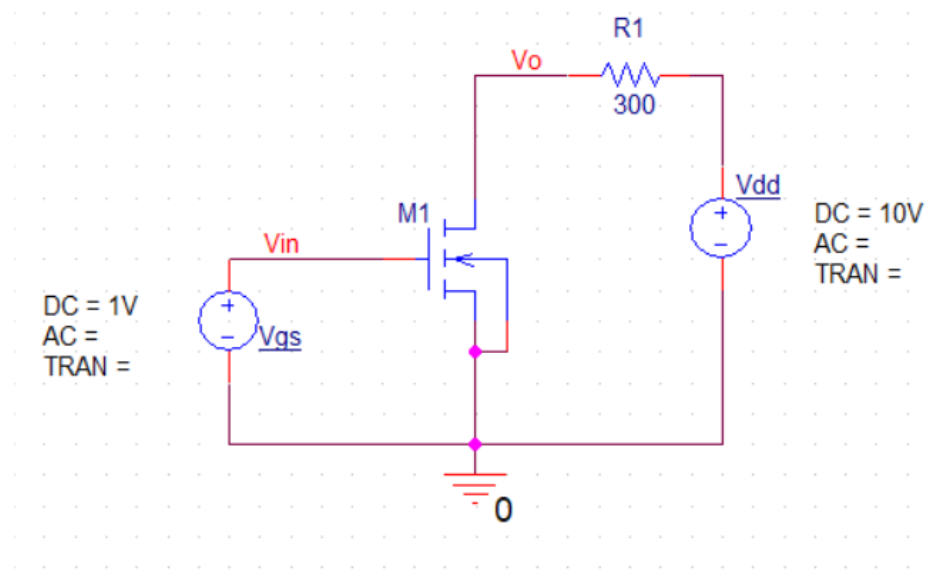
Plot I_d vs V_{ds} @ the chosen 4 V_{gs} points.



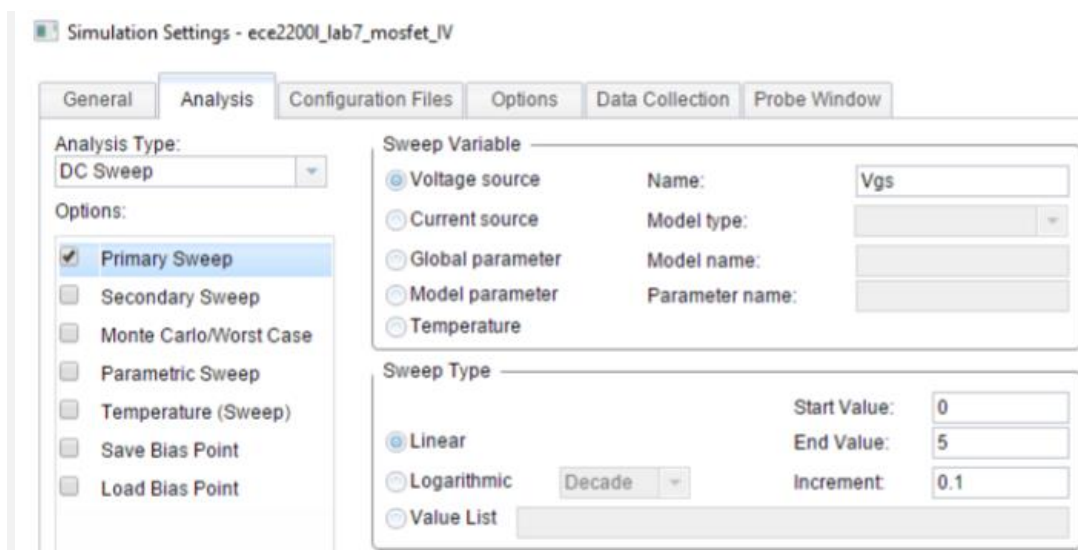
Not straight lines due to channel modulation (more on this in analysis), the resistor acts as an imperfect current source under real conditions. Compared with the simulation plot, where the current source is a much more ideal, straight line.

Id vs Vgs (SIM)

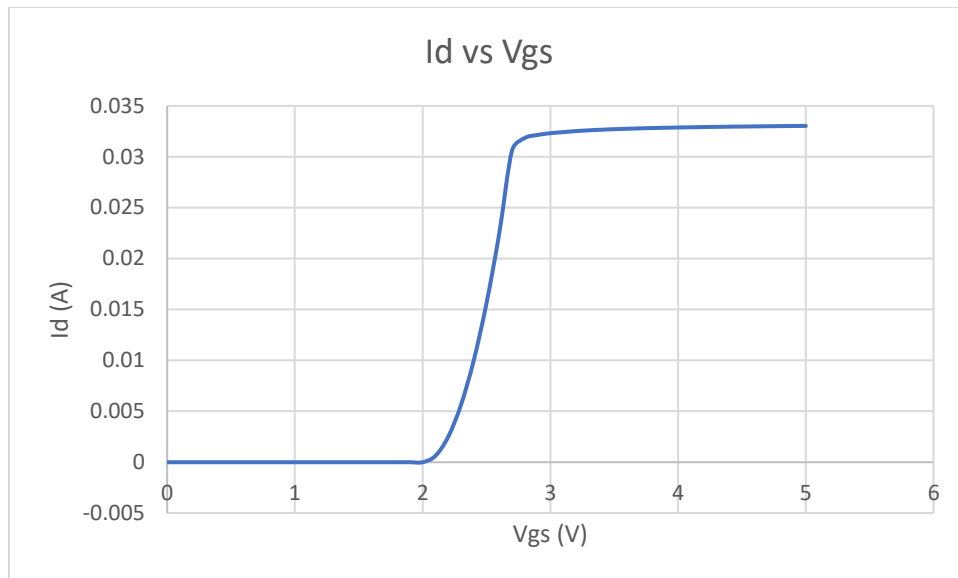
Schematic



Simulation Profile



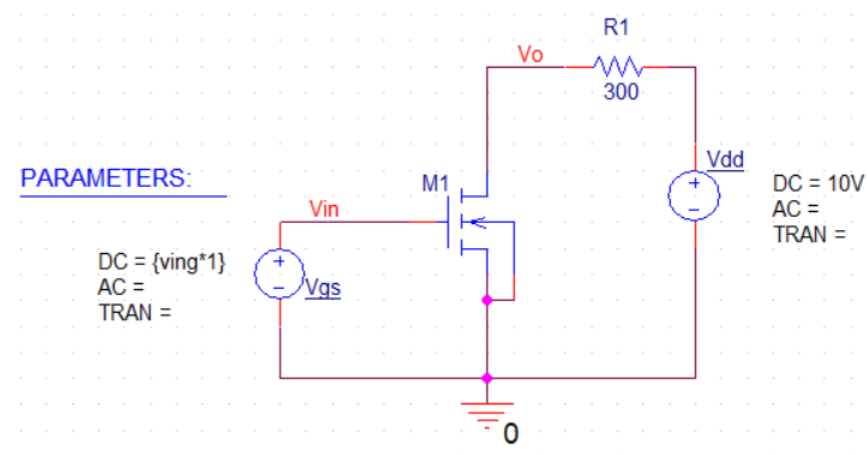
Excel Generated Plots



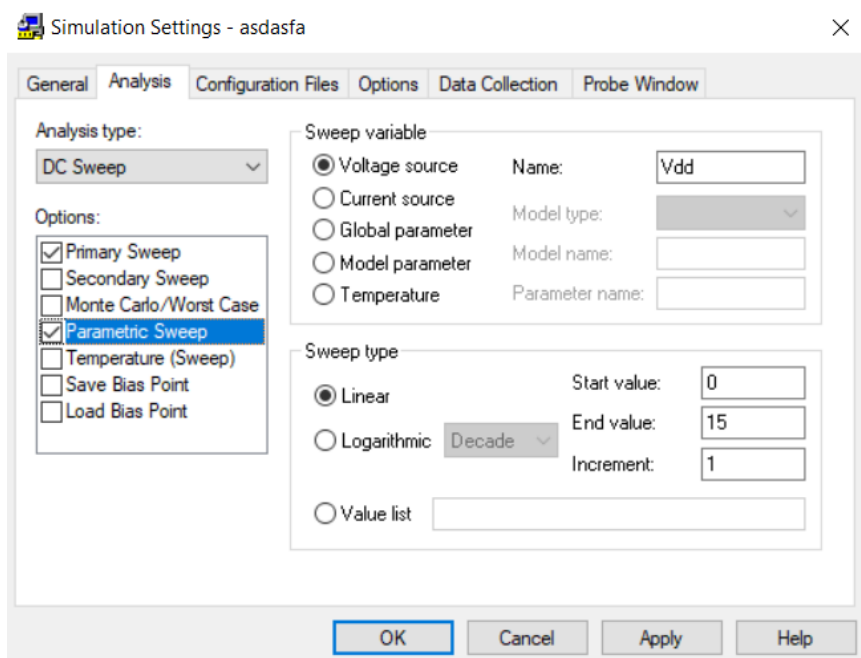
V_{gs} increase doesn't affect I_d until the V_{tn} (or V_{th}) threshold voltage is overcome, this is cutoff mode. Once $V_{gs} > V_{th}$, the MOSFET enters saturation mode and I_d rapidly begins to rise (the "wall" is overcome) until the linear region is reached and the MOSFET's resistance becomes constant.

Id vs Vds (SIM)

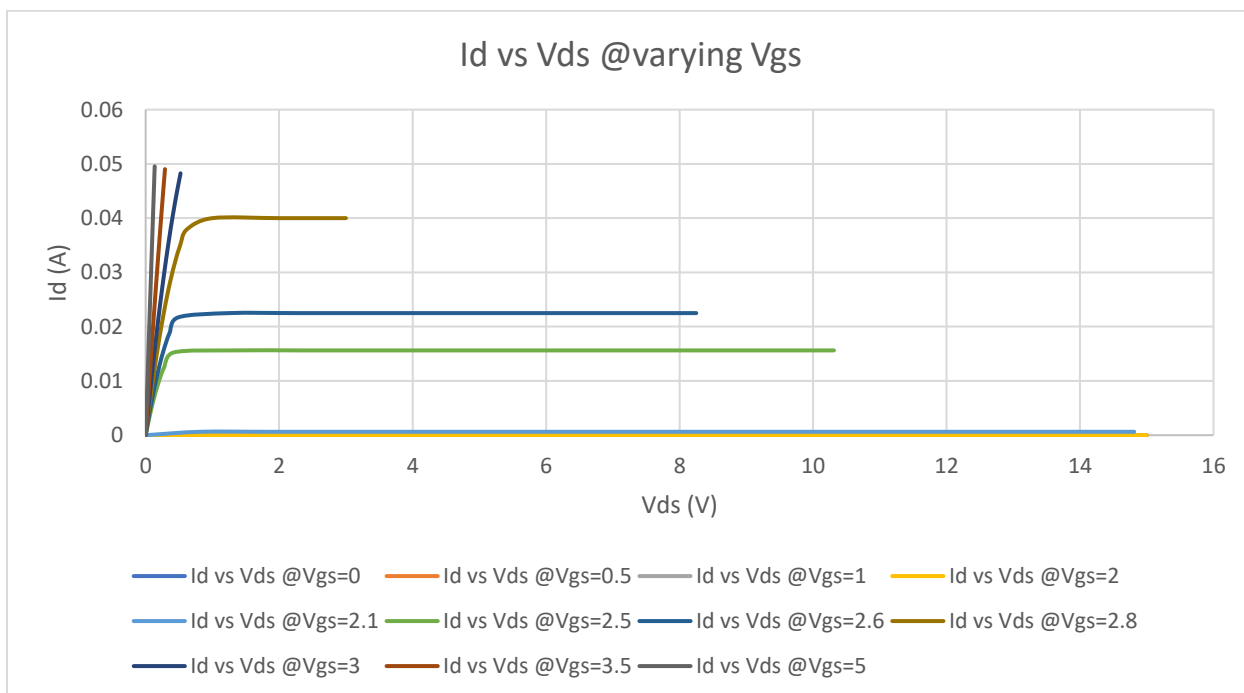
Schematic



Simulation Profile



Excel Generated Plots

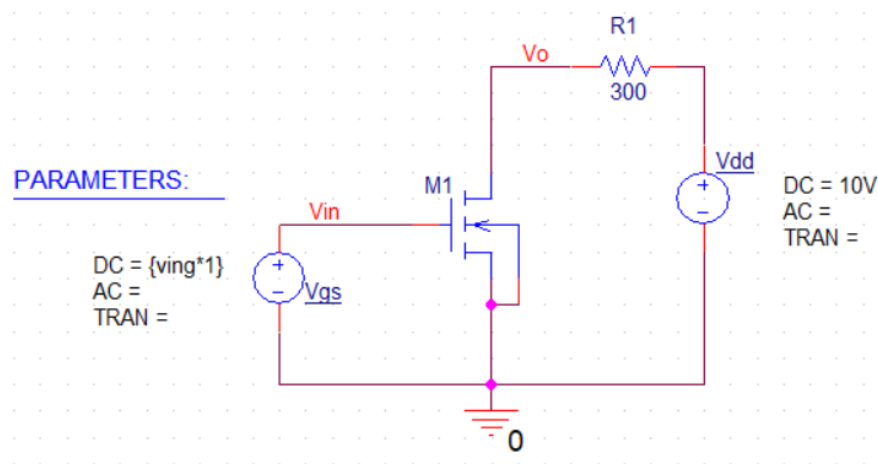


Before $V_{gs}=2.1$ there is no I_d vs V_{ds} change at all. @ $V_{gs}=2.1$, there begins a change in I_d vs V_{ds} plot, a small I_{ds} difference creates an exponential curve leveling off into a straight line.

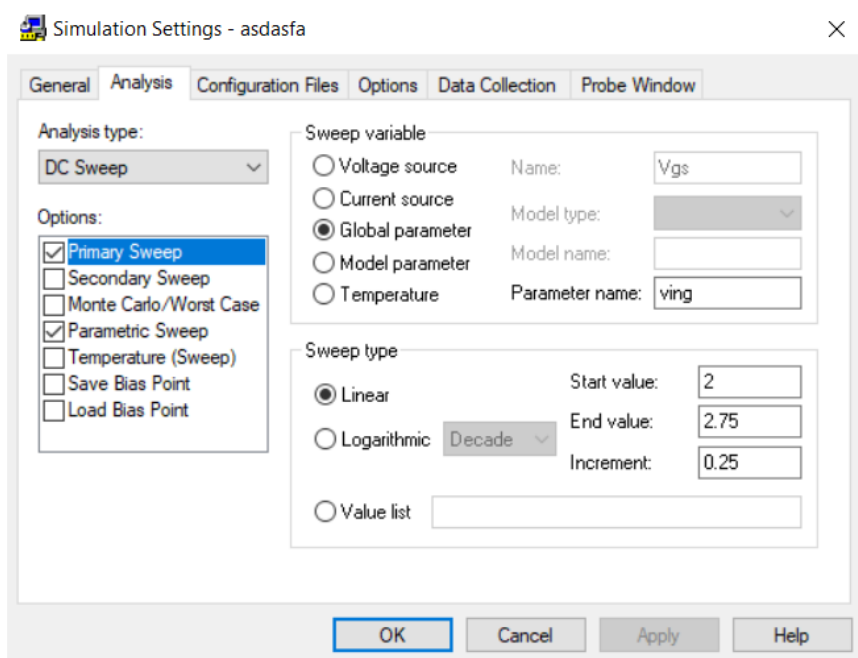
@ $V_{gs}=2.5$ this increase is more noticeable. This shows that I_d is increasing exponentially when V_{gs} increases linearly.

Figure 3 (SIM)

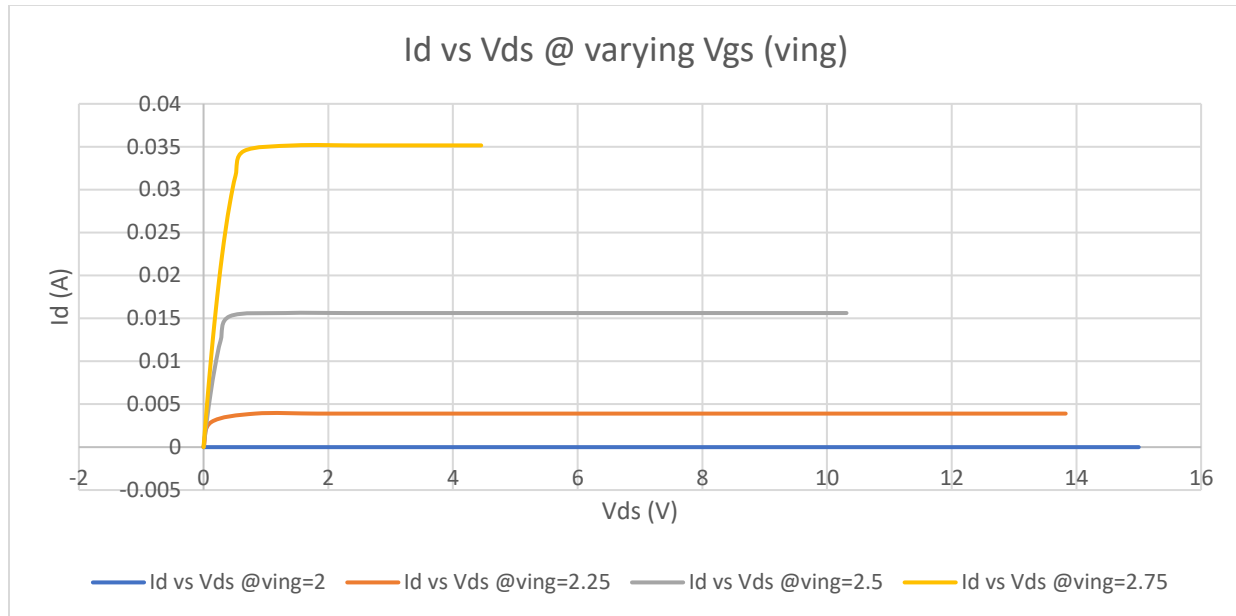
Schematic



Simulation Profile



Excel Generated Plots



At higher input voltage V_{gs} (incrementing linearly), MOSFET acts as an exponentially larger I_{ds} current source, which is perfect (straight horizontal line) under simulation. This is also shown by the earlier I_d vs V_{gs} plot.

Analysis

Firstly, regarding the I_d vs V_{gs} plot, the saturation region mode is perfect for amplification uses because as V_{gs} increases and V_{th} is overcome, the MOSFET becomes like a resistor (looks like an imperfect pure voltage source), amplifying the input V_{gs} voltage into a high output V_{ds} (through a high I_{ds}). Ideally, in this region I_d is completely dependent on V_{gs} only, not V_{ds} as shown in the saturation equation. After pushing V_{gs} too high, linear mode is reached. V_{gs} (or V_{dsat} which is $V_{gs}-V_{th}$) becomes greater than V_{ds} , and I_d stops increasing exponentially. This behavior in the linear region is like a voltage-controlled resistor controlled by V_{gs} , where the resistance is maintained as constant no matter how large V_{gs} becomes. As mentioned in the

relevant section, the relationship between V_{gs} and I_d is nonproportional, I_d increases are exponential when V_{gs} increases are linear. This can be seen in the second simulation plot, where the I_d difference between $V_{gs}@3$ and $@3.5$ is ~ 0.022 A and ~ 0.04 A, I_d almost doubles, while V_{gs} increases by $\sim 17\%$. For the I_d vs V_{ds} plots, the difference between real and simulated conditions are most noticeable in the linear region where the MOSFET's I_d vs V_{ds} relationship begins to look like a current source: as expected, the lab data yields an imperfect sloped line as opposed to the perfect horizontal line of the simulation data, which is a result of the channel modulation between the source and drain N regions. That is, the increase of V_{ds} controls the width of channel between the source and drain, which results in a small increase in the I_d as V_{ds} increases only under real conditions. Note that the transition region between linear and saturation

modes is parabolic, governed by the linear equation:

$$I_{DS} = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2} \right] (1 + \lambda V_{DS})$$

(the saturation equation is also valid), which shows the initial exponential relationship between V_{ds} and I_{ds} .

Addendum or Reference

Excel Generated Data (some datasets may be linked if too large)

Lab Data: [2200L-L7lab.xlsx](#)

^(includes I_d vs V_{gs} Plot & I_d vs V_{ds} @varying V_{gs} Plot)

Simulation 1: [2200-L7model1.1.xlsx](#)

Simulation 2: [2200L-L7model2.1.xlsx](#)

Simulation 3: [2200-L7model3.xlsx](#)